

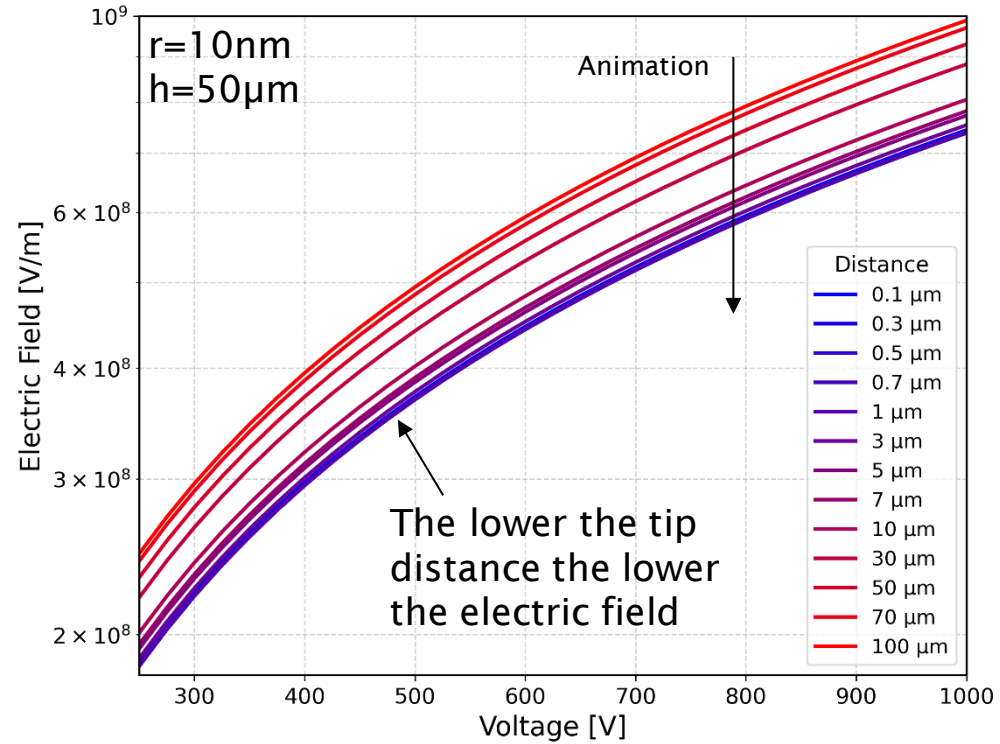
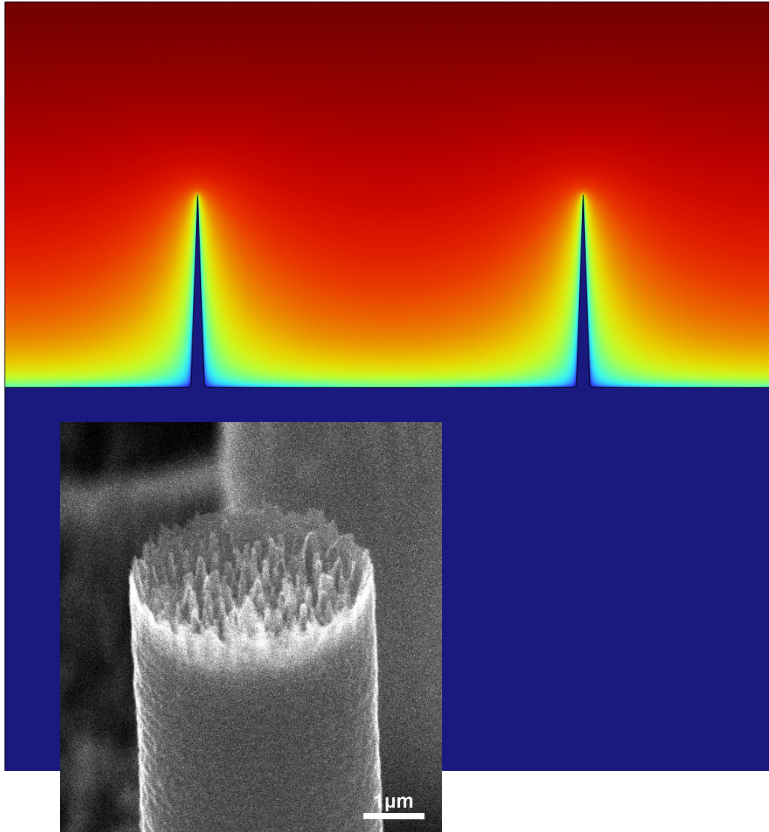
AN OVERVIEW OF THE DEVELOPMENT OF SILICON NANOWIRE ELECTRON SOURCES

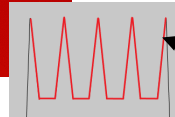
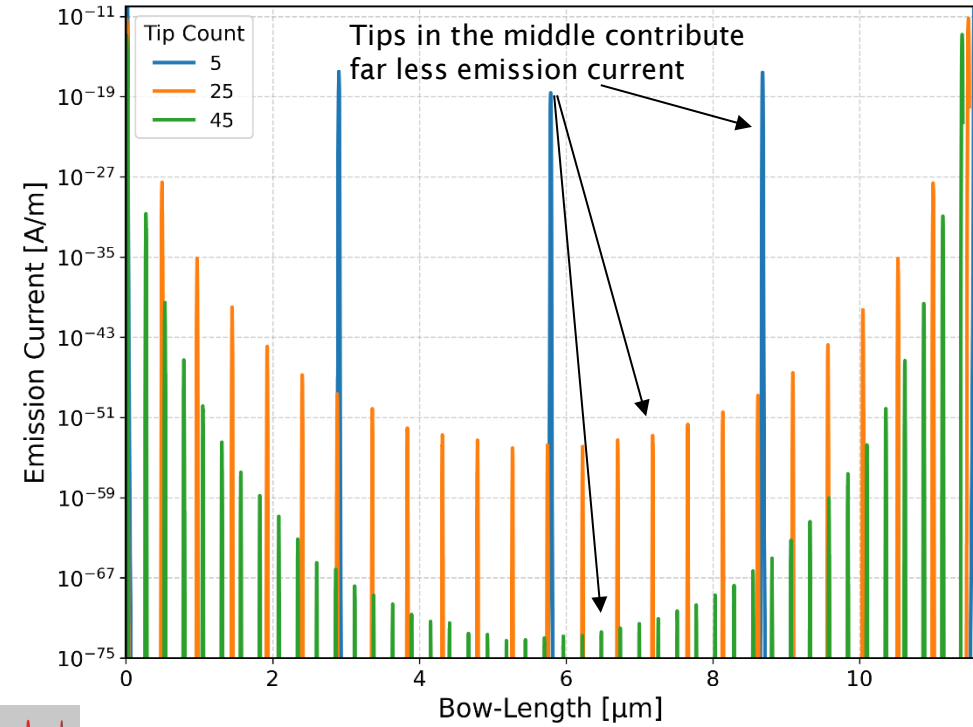
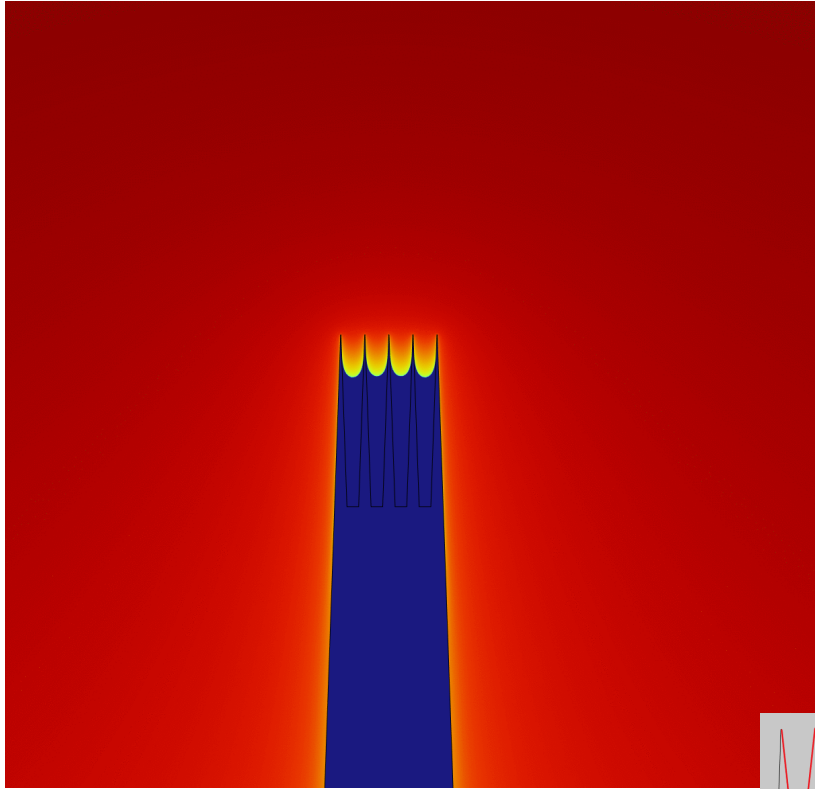
Philipp Buchner, Matthias Hausladen, Mathias Bartl, Ali Asgharzade, Markus Langmantel, Josef Sellmair, Kamil Baranowski, Michal Krysztof,
Daniel Burda, Alexandr Knápek, Dennis Kepic, Simon Edler, Andreas Schels
and Rupert Schreiner

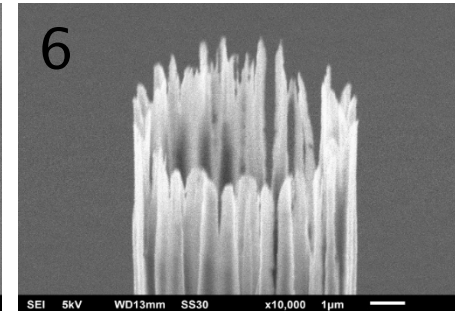
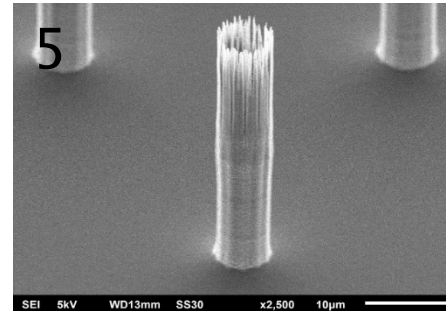
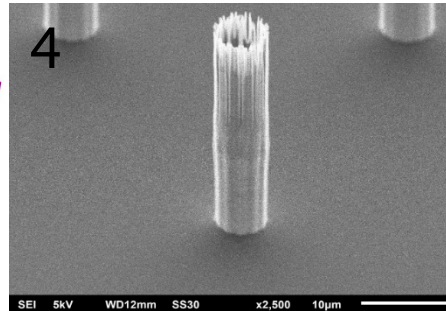
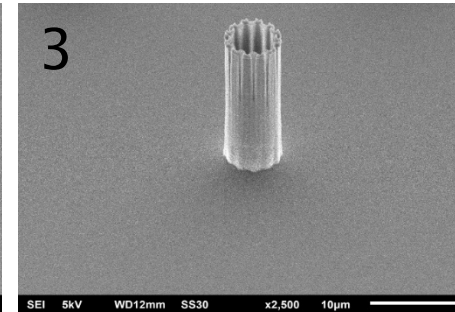
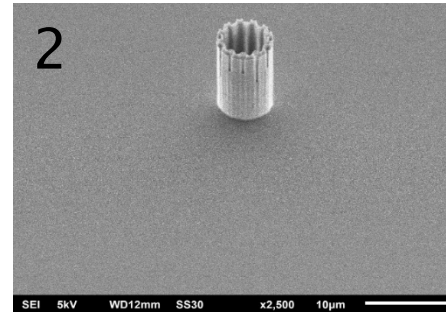
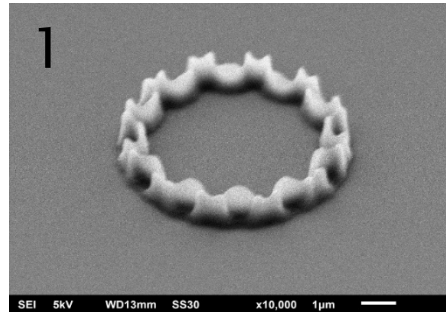
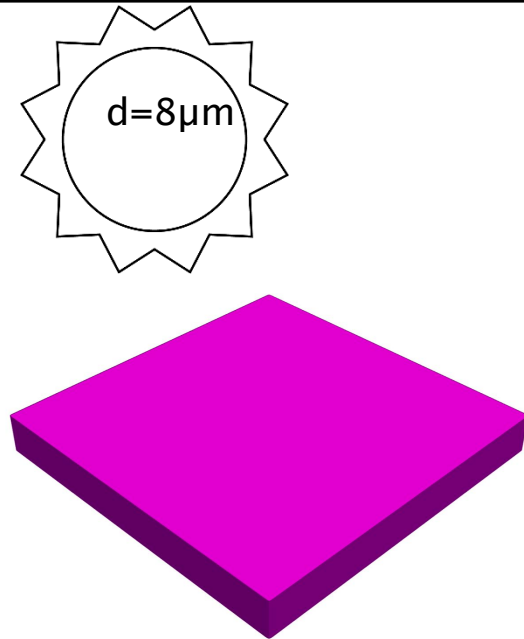
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10th VDE ITG International Vacuum Electronics Workshop (IVEW) 2026

29. August 2026





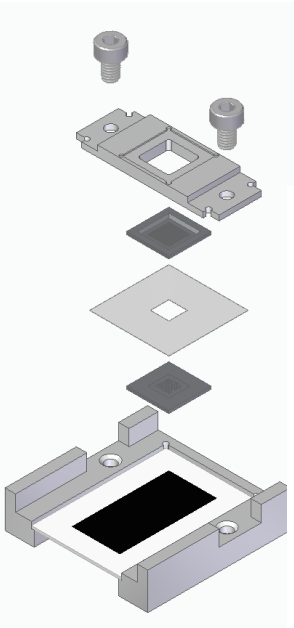


Emitter structured by a four step process:

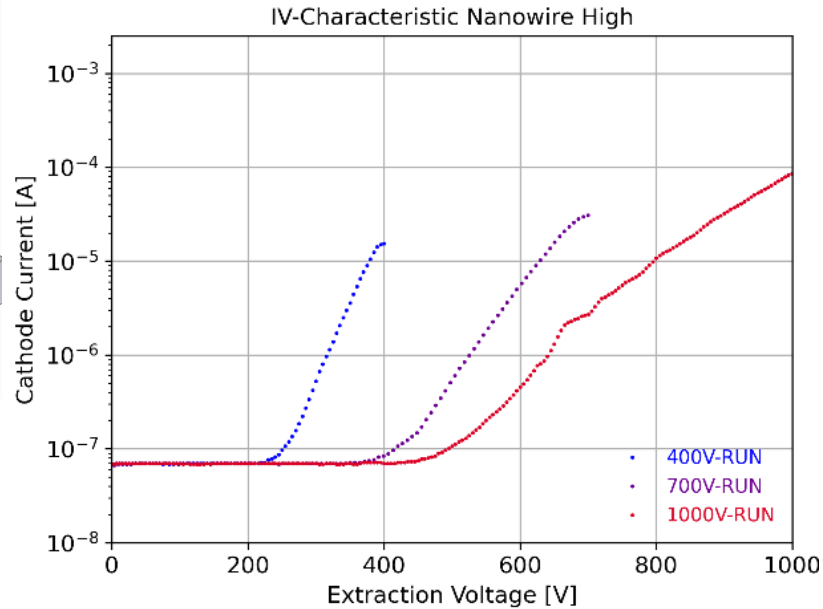
- generating an irregular ring of photoresist
- anisotropically etching the silicon
- removing the photolaquer
- repeating the etching step

Two types of silicon used:

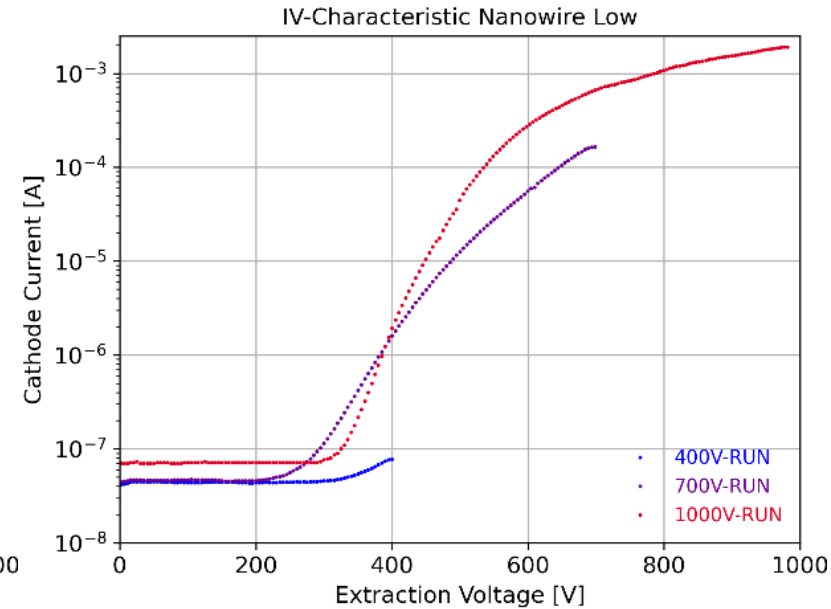
- n-Type (Ph), $\langle 100 \rangle$, 1-10 Ωcm
- n-Type (Ph), $\langle 100 \rangle$, $<0.005 \Omega\text{cm}$

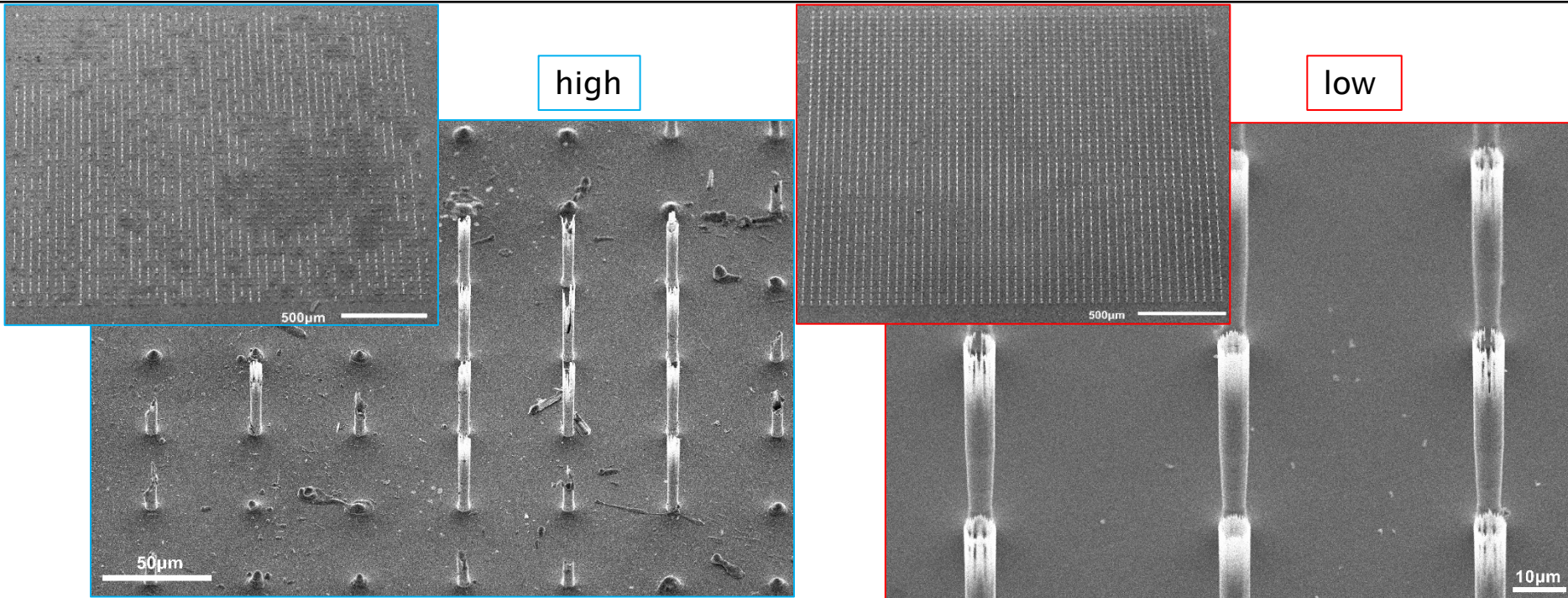


- n-Type (Ph), $\langle 100 \rangle$, $<0.005 \Omega\text{cm}$

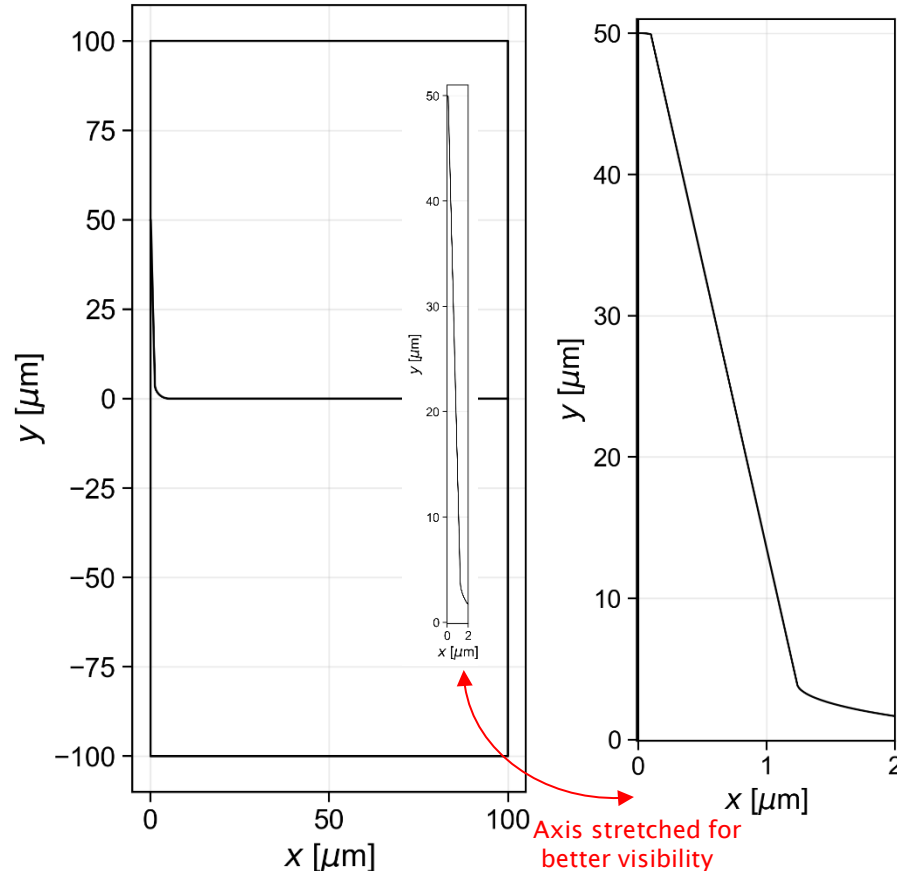


- n-Type (Ph), $\langle 100 \rangle$, $1-10 \Omega\text{cm}$

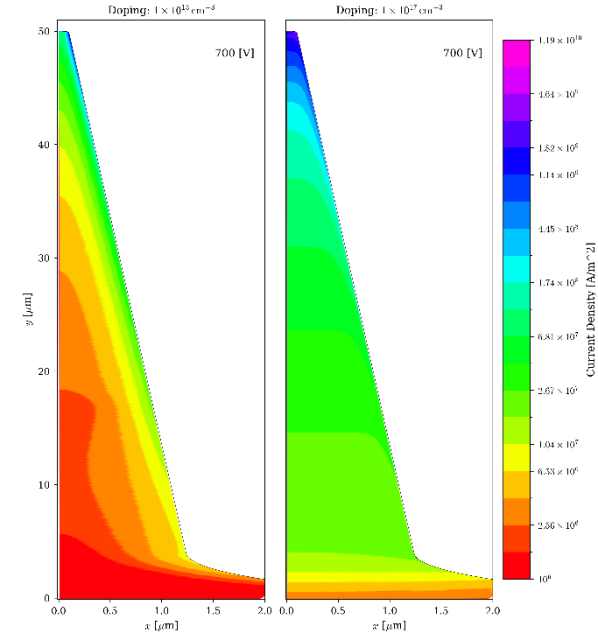
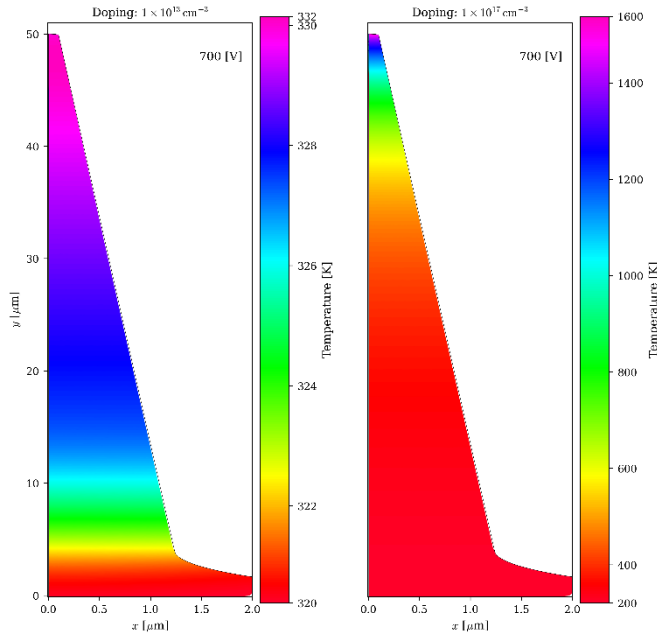




- SEM images after measurement show strong degradation for highly doped silicon samples
- Lowly doped samples show virtually no degradation in SEM images after measurements
- → Unregulated rise in current leads to thermal runaway for high doped emitter



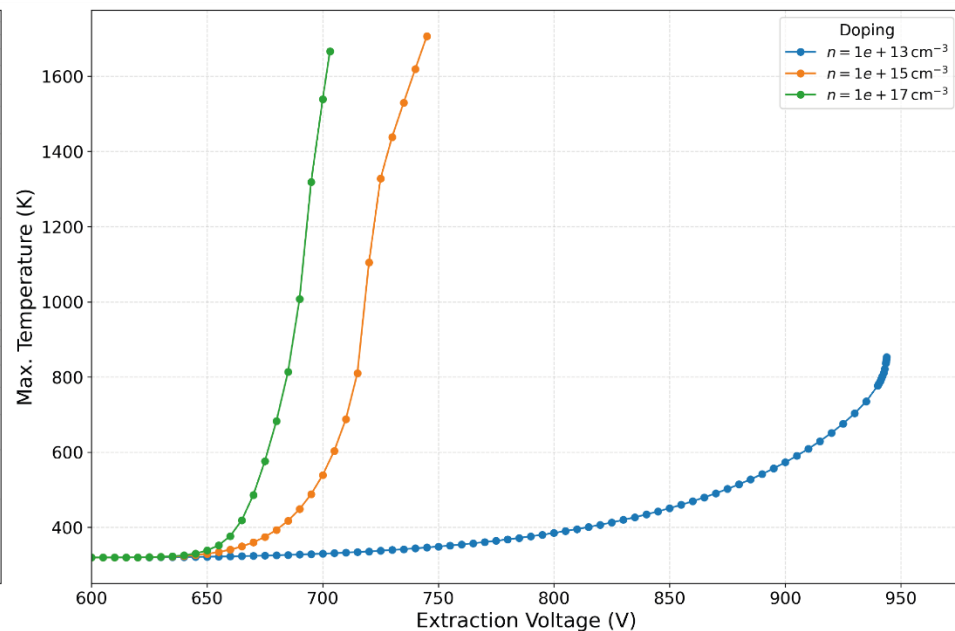
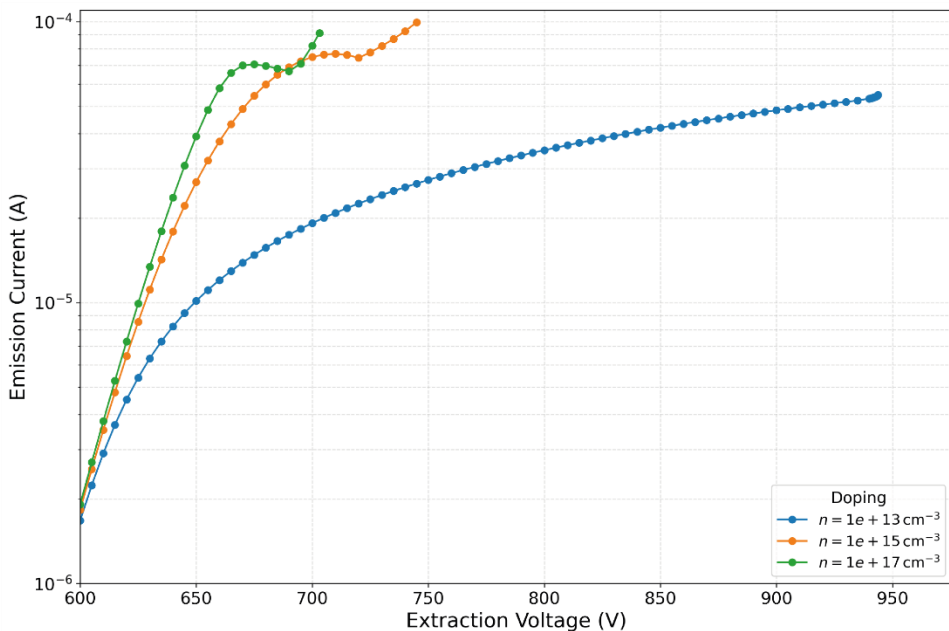
- Semiconductor module
 - Electric fields
 - Field emission (modified)
 - Electron concentration (Temperature)
 - Electron mobility (Temperature)
 - Generation/Recombination (Temperature)
 - Surface states and recombination
 - Permittivity
- Electric currents
 - Voltage drop due to resistivity
- Heat transfer in solids
 - Joule heating due to current and resistivity
 - Nottingham Effect due to Field Emission
 - Radiative cooling
 - Convective cooling
 - Heat conduction
- Sweeps of extraction voltage for different doping levels

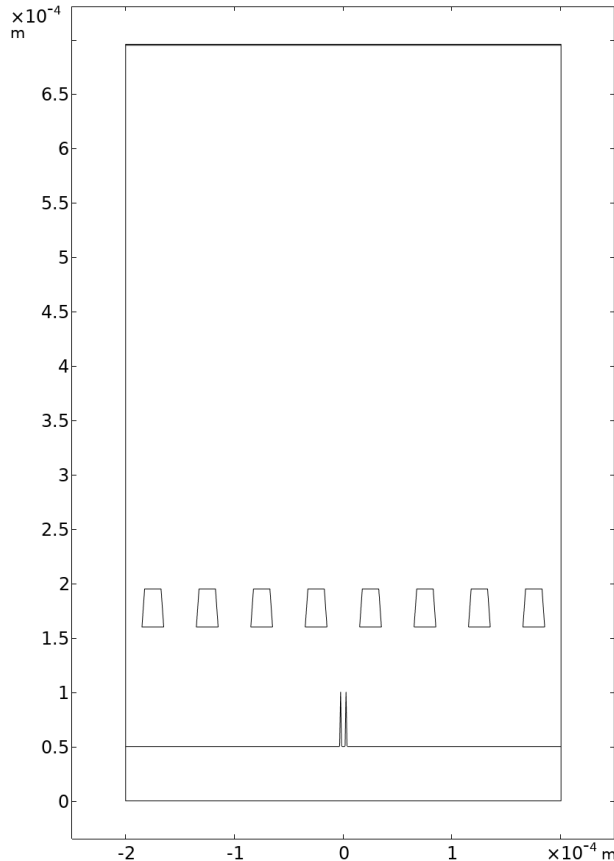


- **High doped** emitter heats up more locally and gets therefore hotter in a smaller volume
- **Low doped** emitter heats up more evenly and therefore reaches lower temperatures

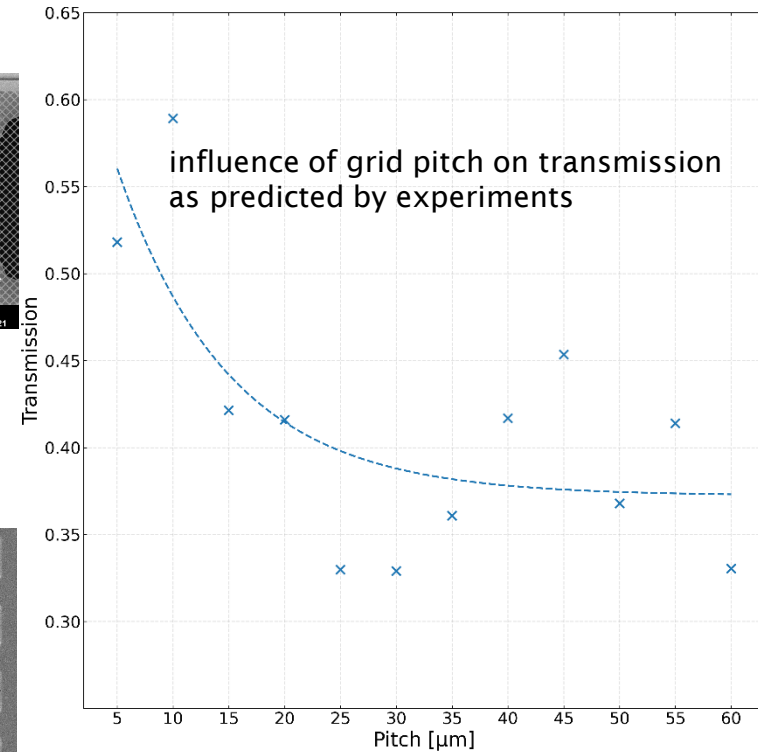
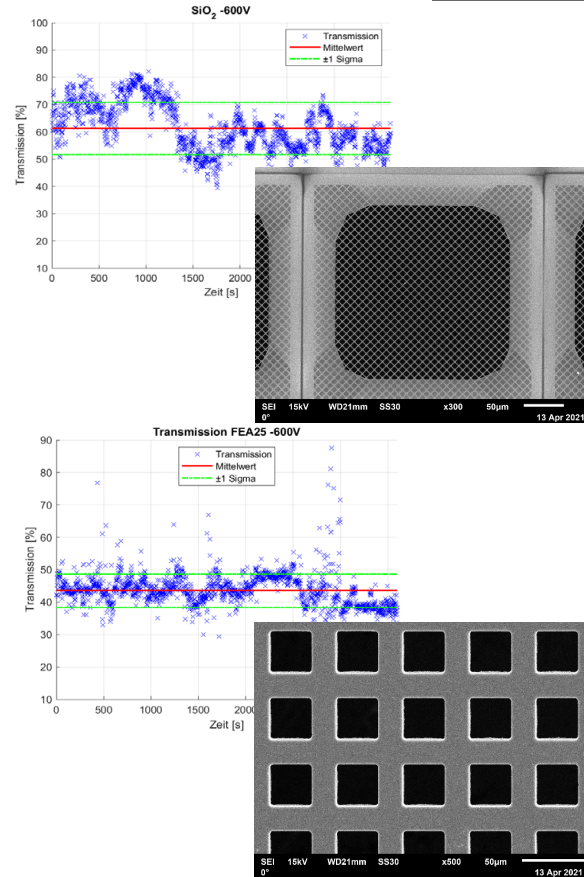
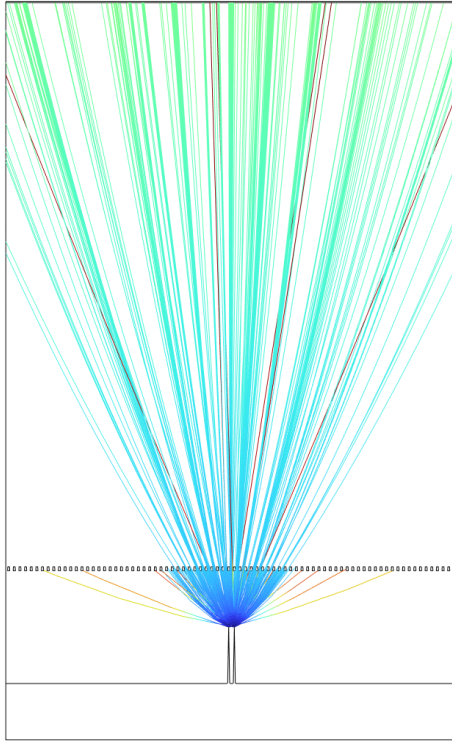
Note: same geometry and extraction voltage only difference: doping level

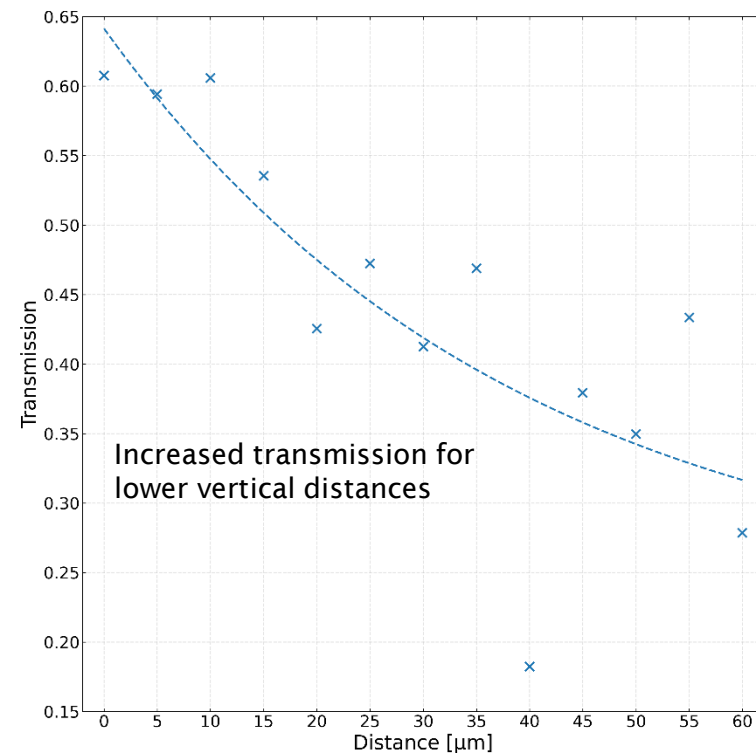
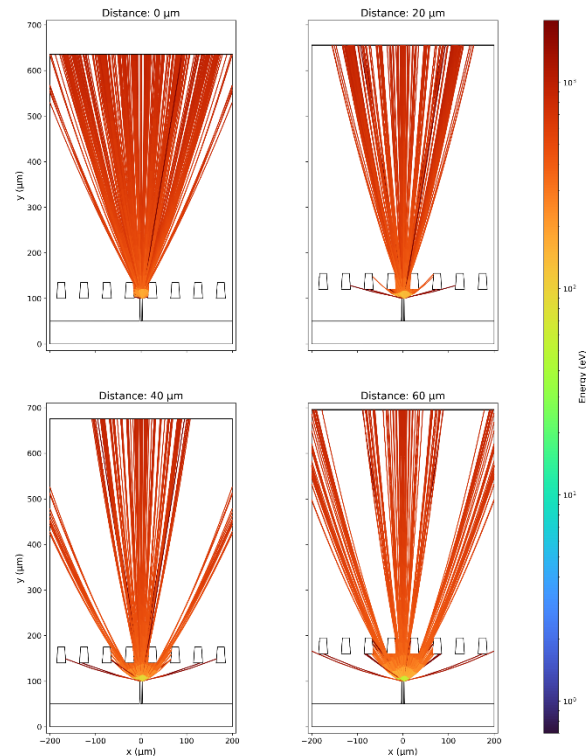
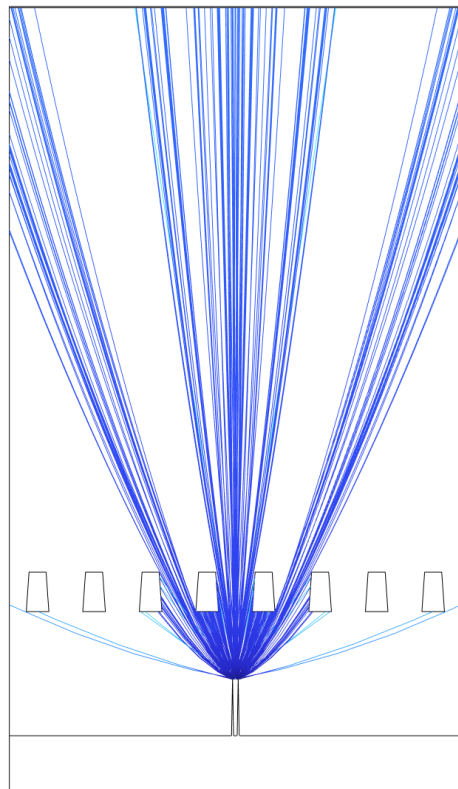
- **High doped** emitter: the whole bulk conducts electrons
- **Low doped** emitter: only the edge conducts

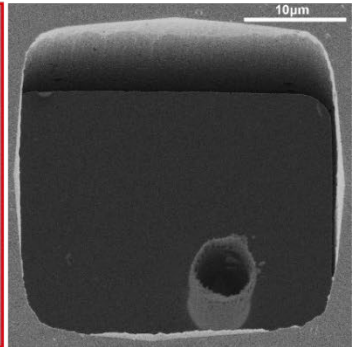
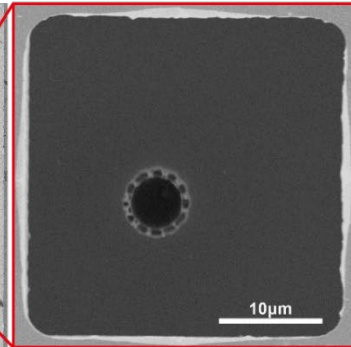
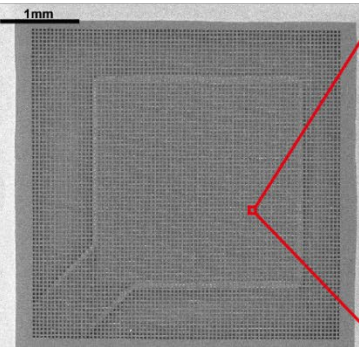
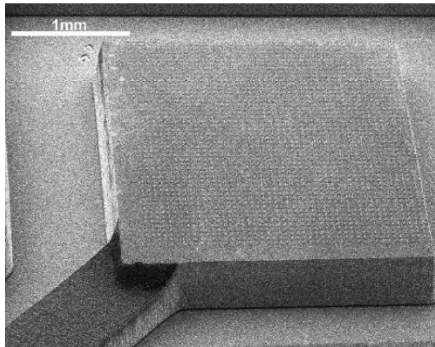
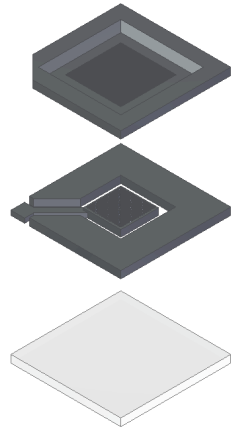
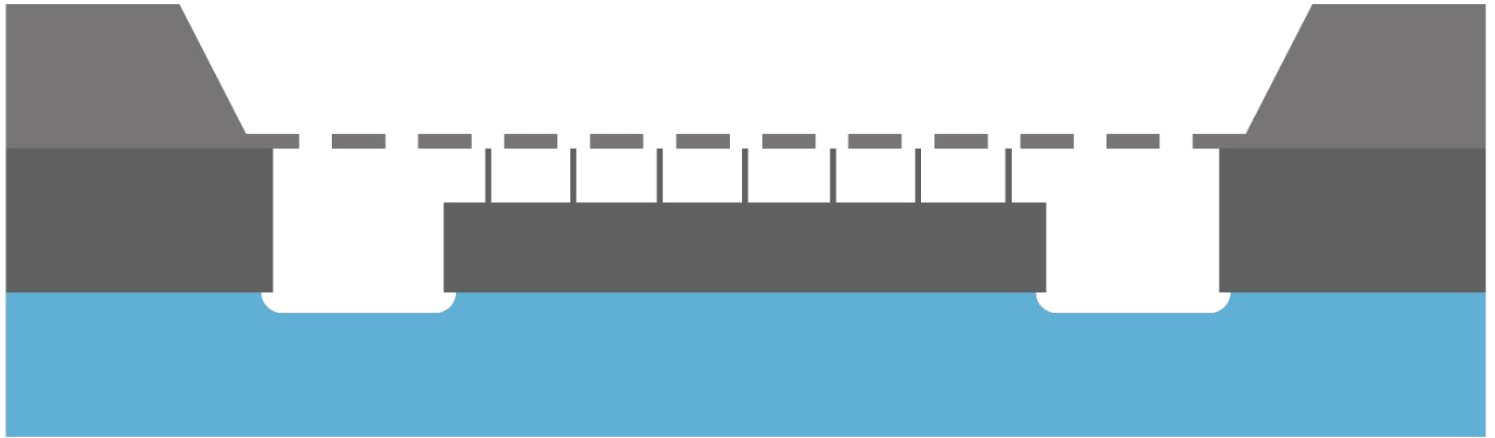
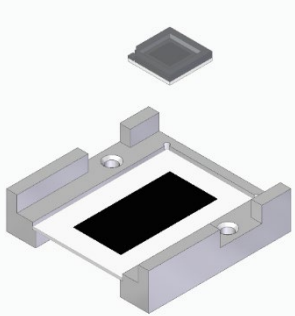




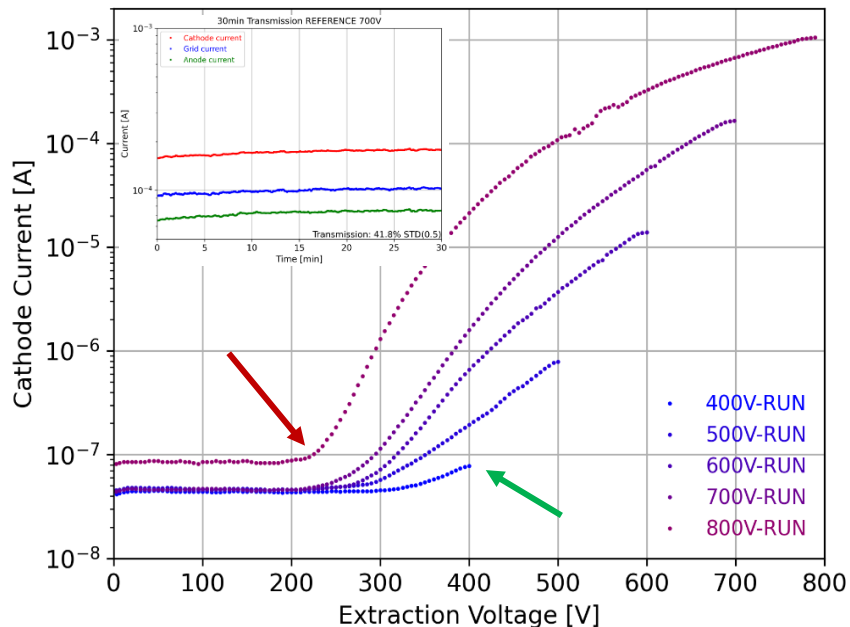
- Electric fields, semiconductor properties and cathode geometry as described before
- Coupled to charged particle tracing module
 - 10 electrons per released particle
 - 0 – 400ps in 2.5ps steps
 - Number of released particles calculated by FE-Boundary Condition
- Extraction grid geometry controlled by parameters
- Multiple studies varying geometries



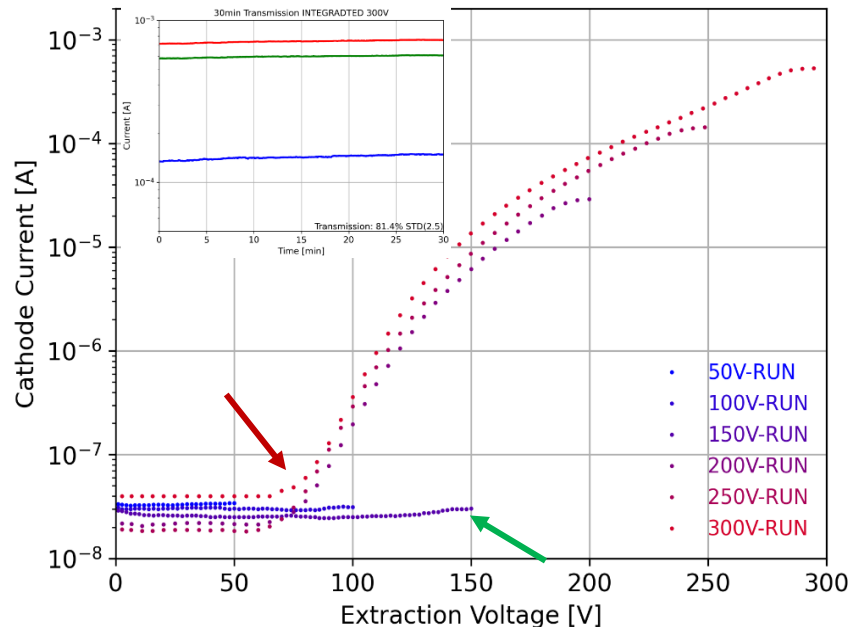




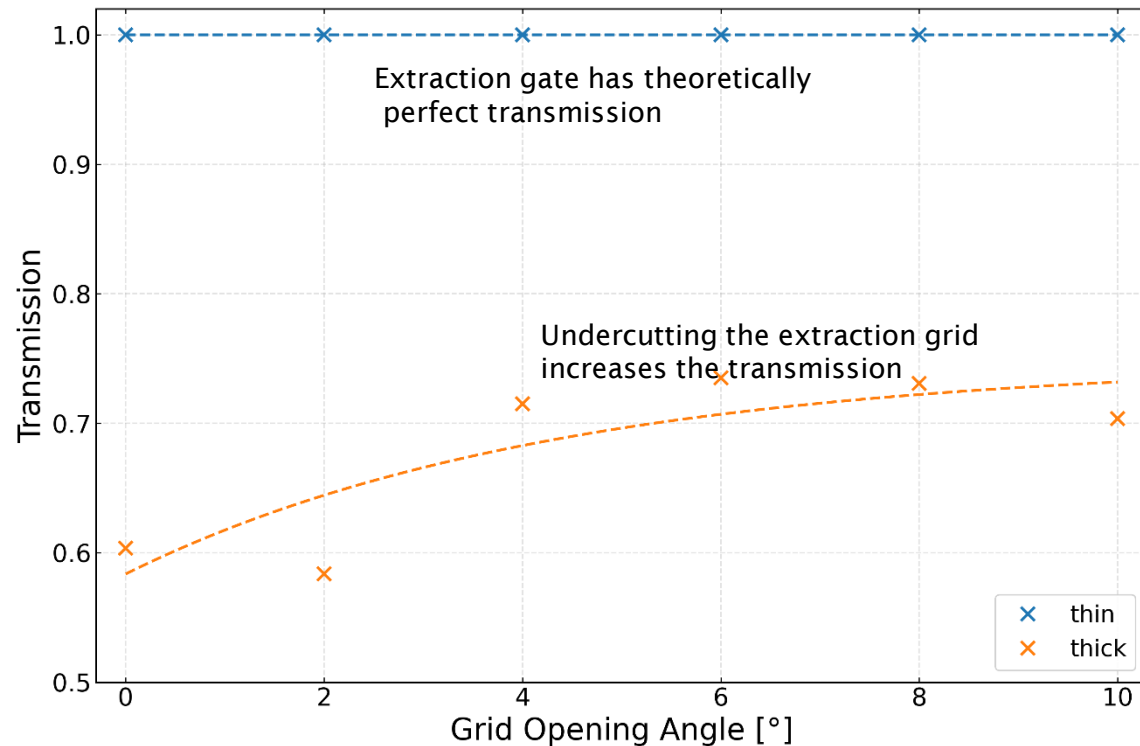
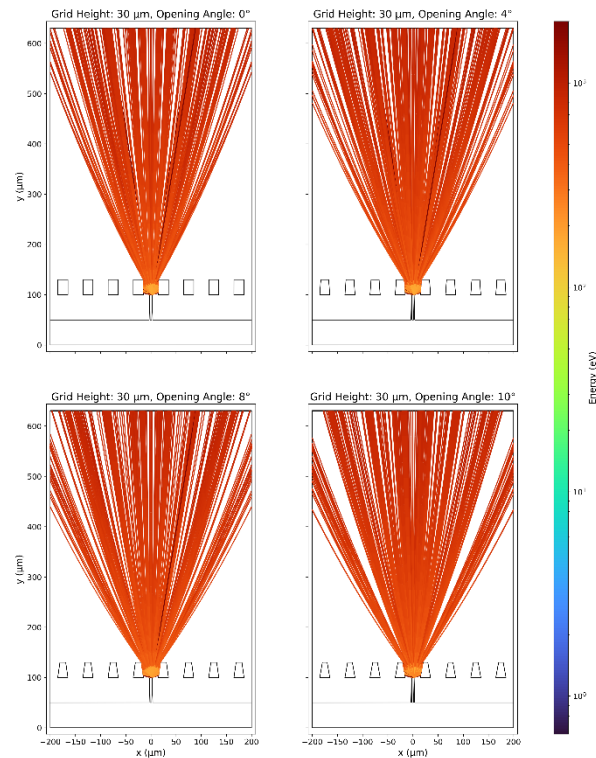
Characteristic Activation REFERENCE

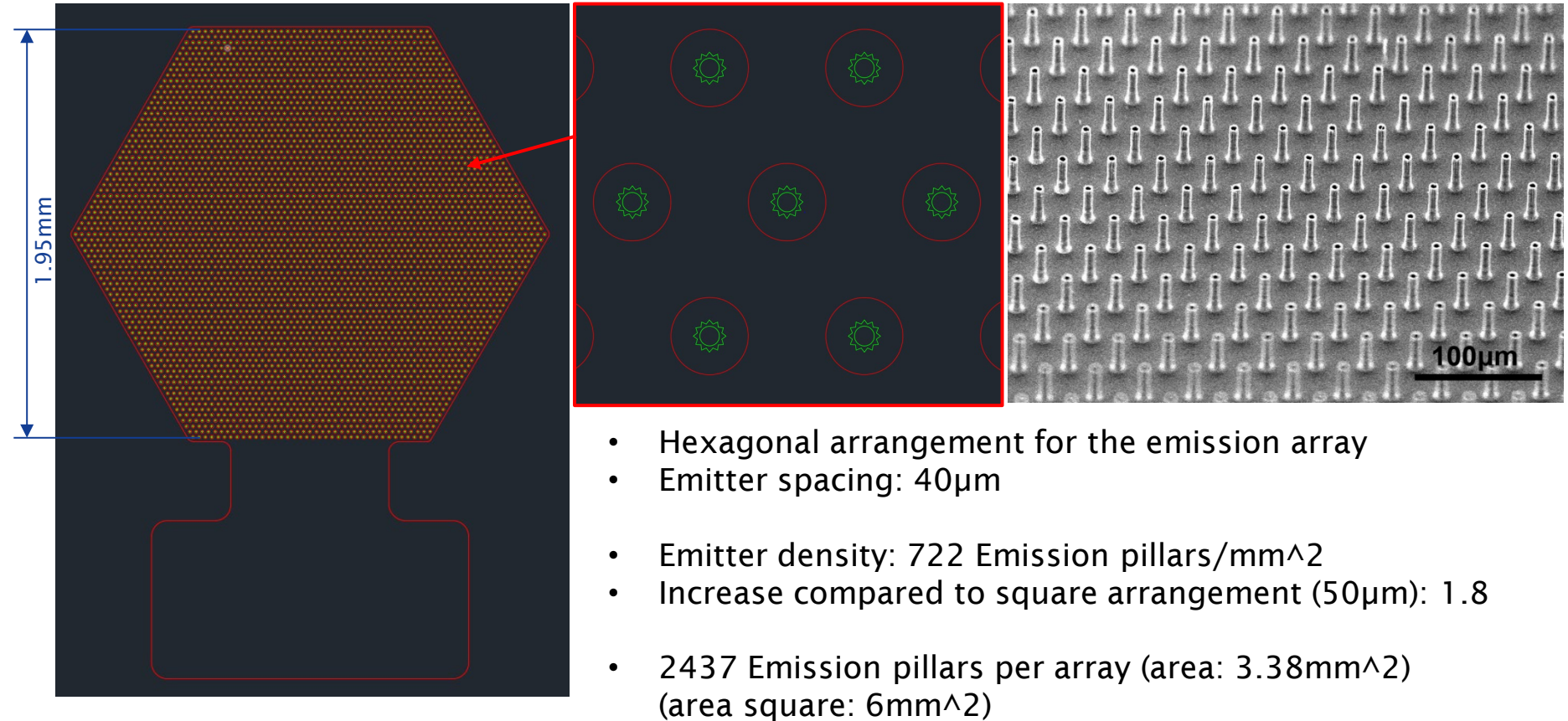


Characteristic Activation INTEGRATED

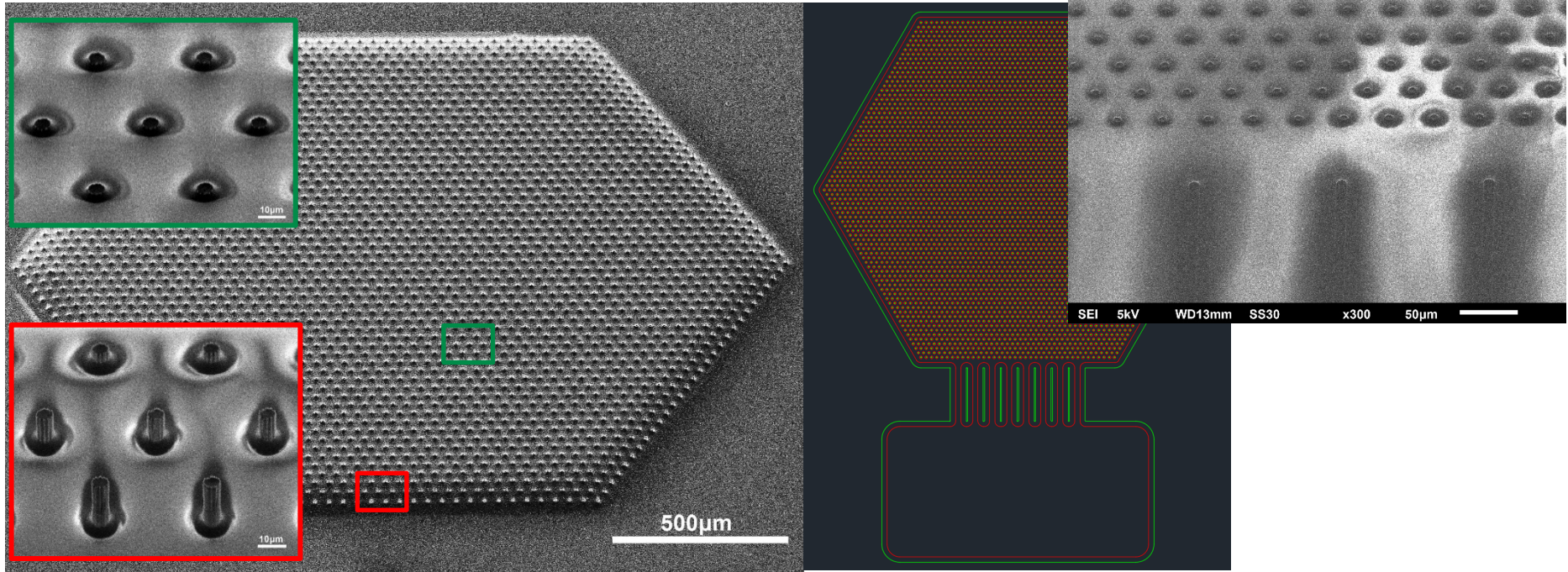


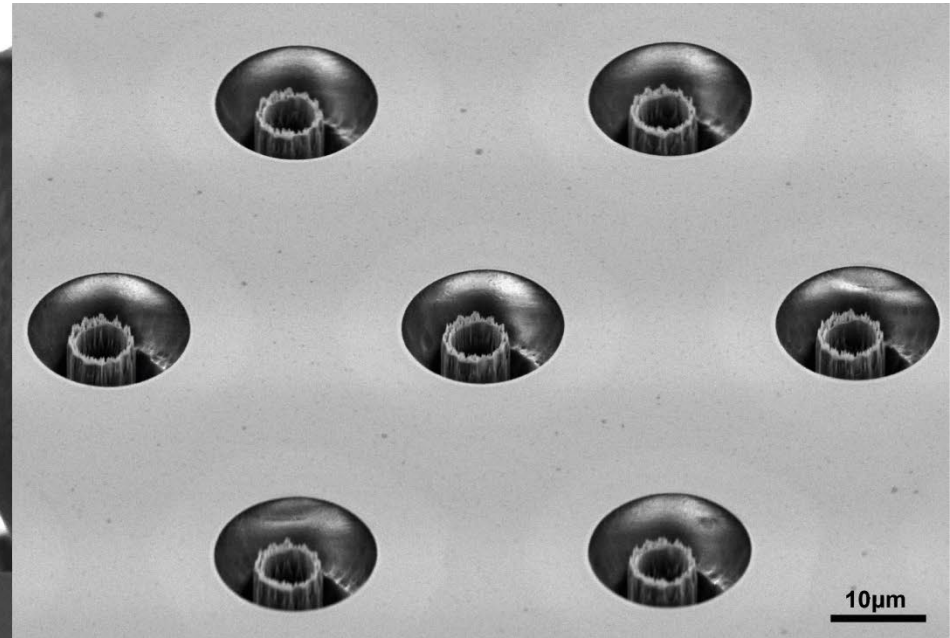
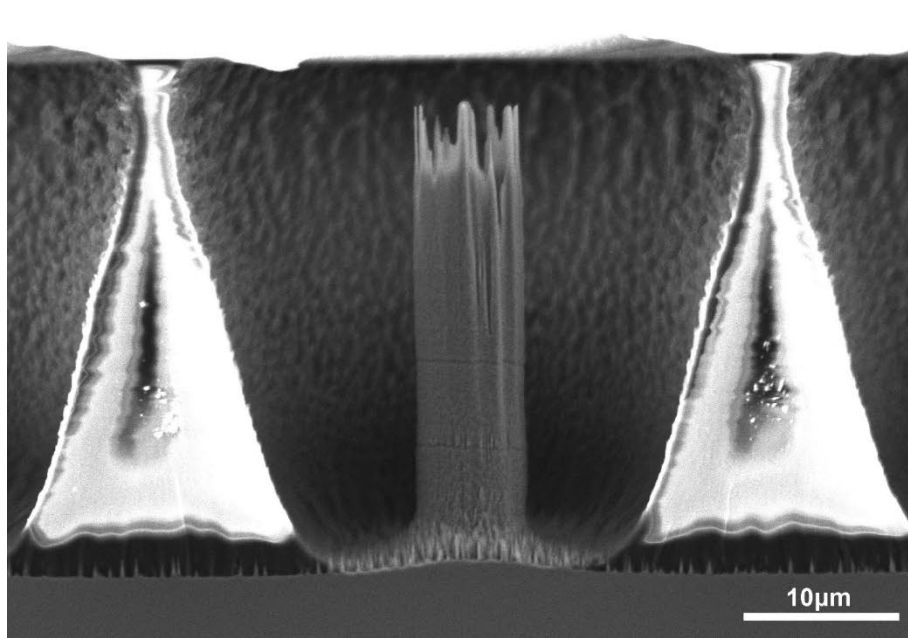
- Onset voltage reduced by 200 V (from ~300V to 75V)
- First emission at 150 V with new sample (old one 400 V)
- About 700 μ A emission current at 300V (old sample same level at 700V)
- Transmission of 41.8% (StD: 0.5%) with the mica spacer due to missalignment
- Glass insulation path: transmission of 81.4% (StD: 2.5%)

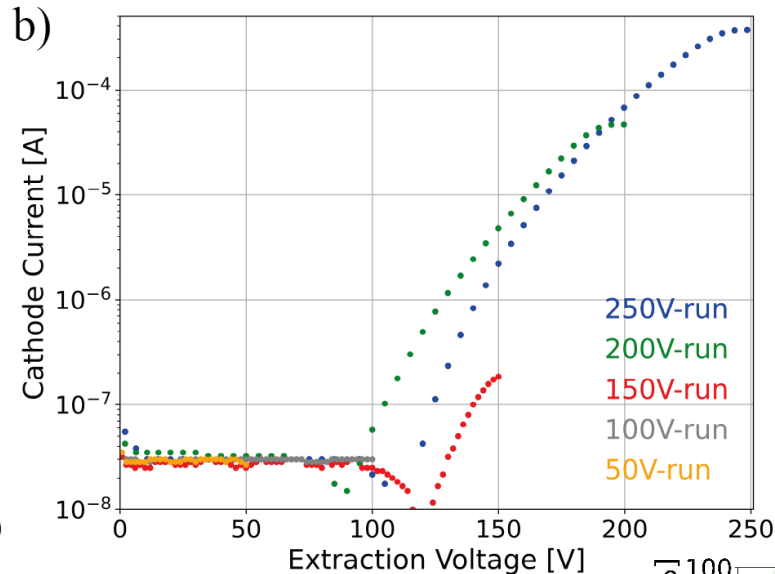
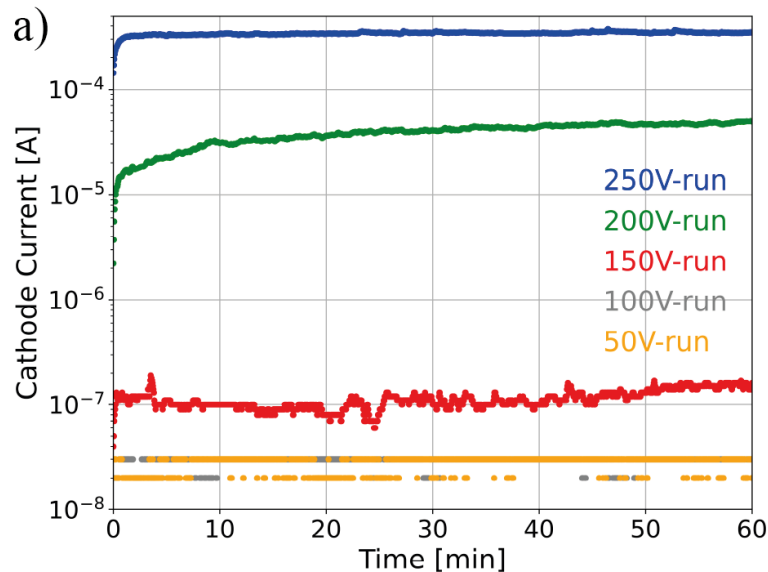




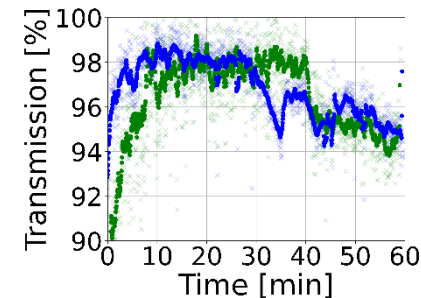
- Irregular coverage with BCB due to flow resistance at the border of the array
→ New mask with the emitters sunken into a valley







- 400 μ A of emission current reached at 250V extraction voltage
- the best transmission figures reached were:
 - Anode voltage 500V
 - Cathode voltage 200V/250V
 - Average transmission: 97% over measurement periode



Any Questions?

